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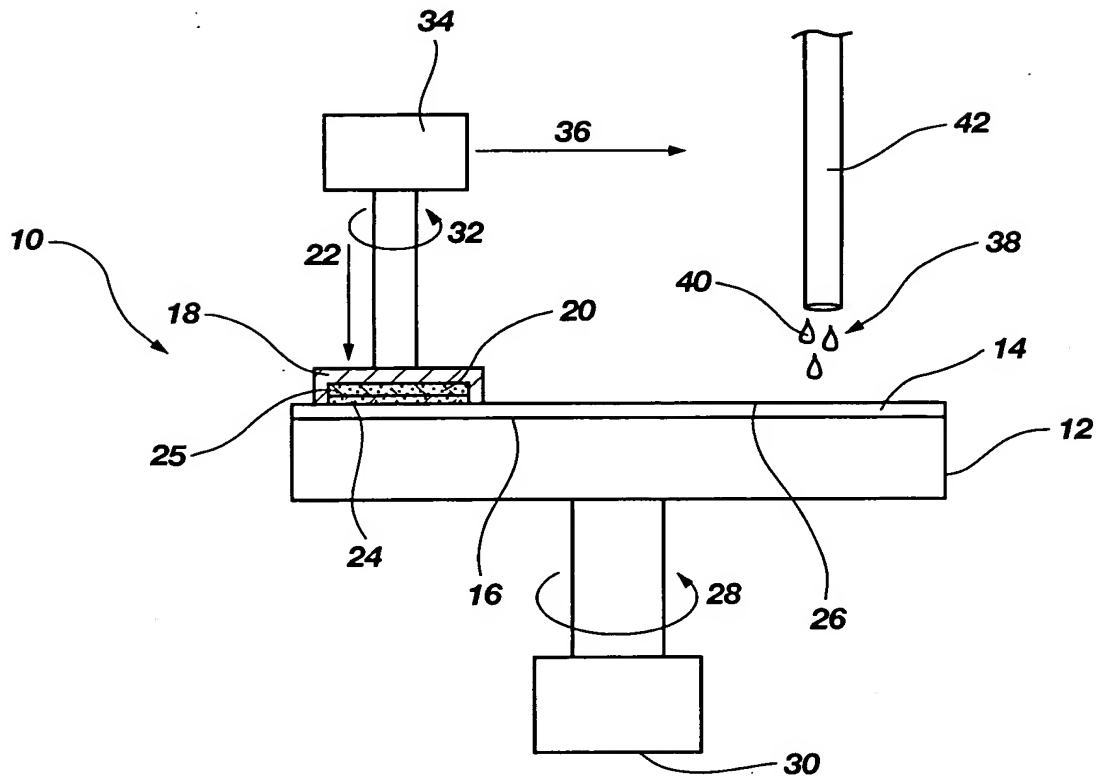


Fig. 1A

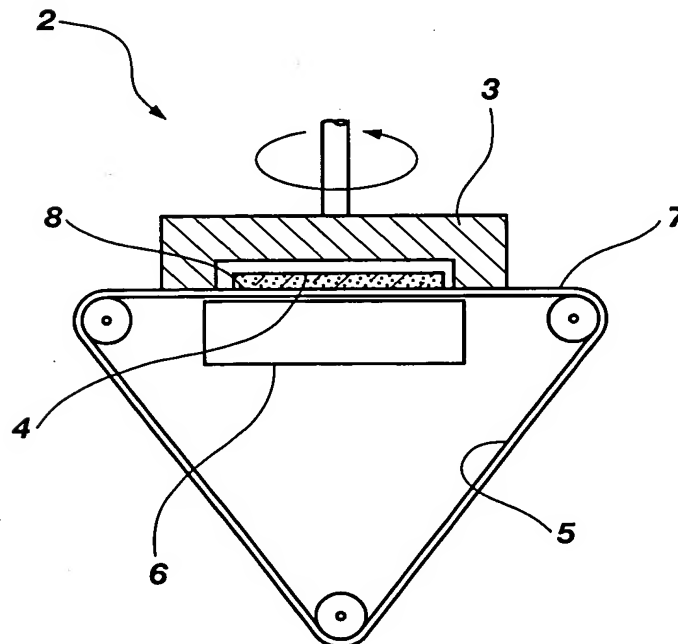


Fig. 1B

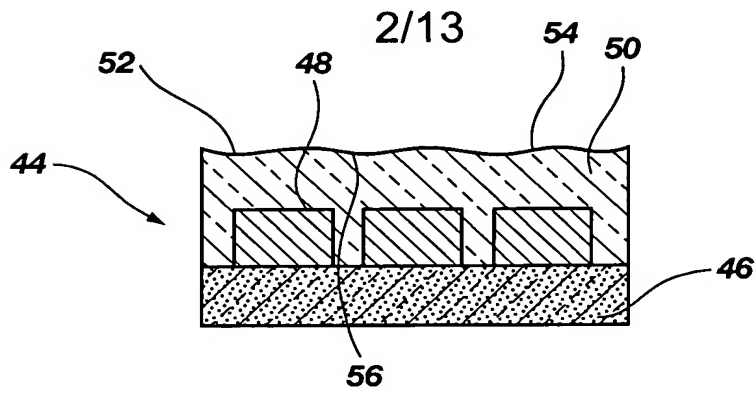


Fig. 2

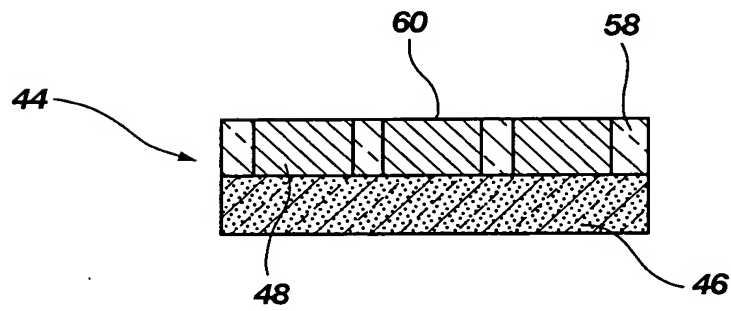


Fig. 3

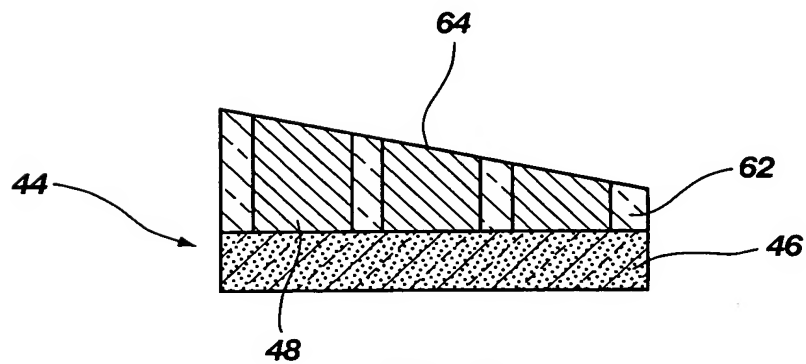


Fig. 4

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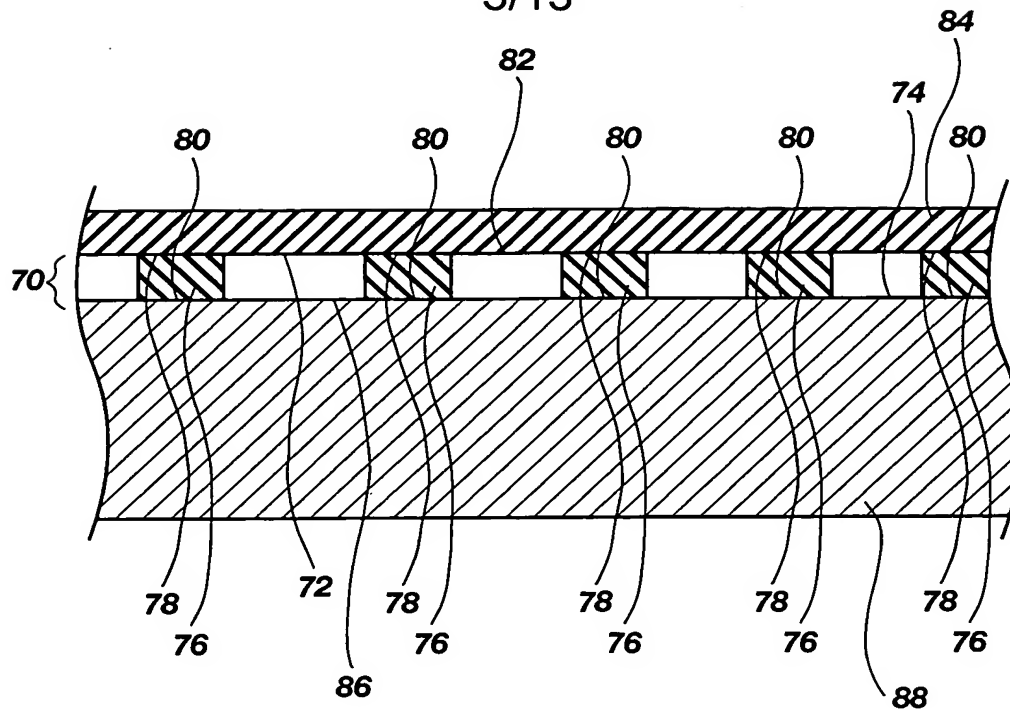


Fig. 5

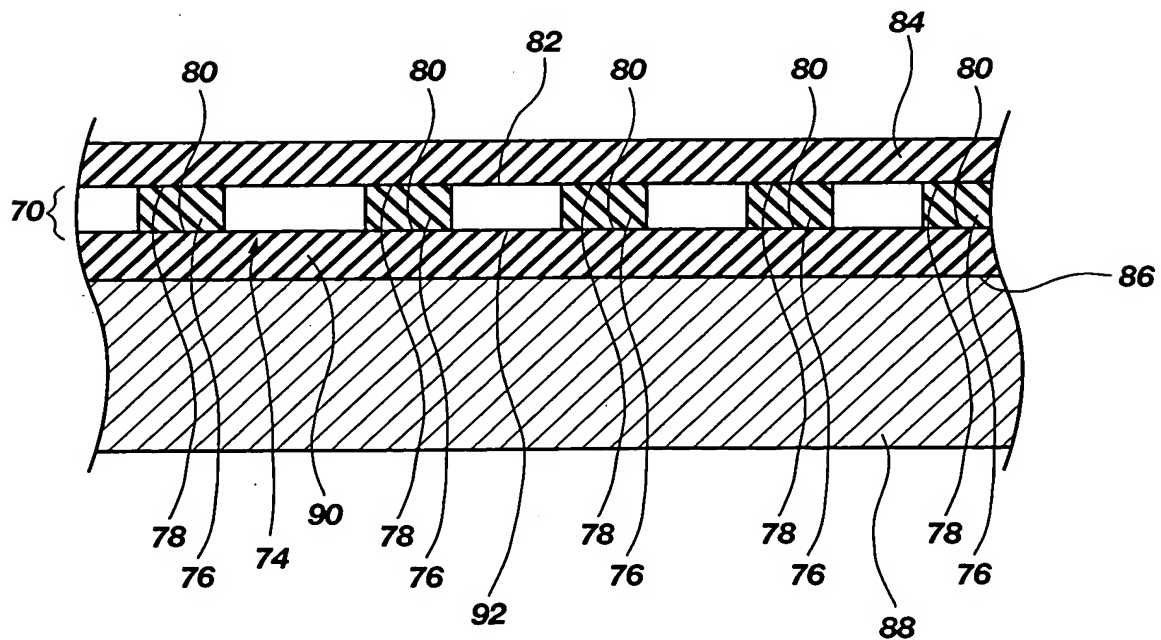


Fig. 6

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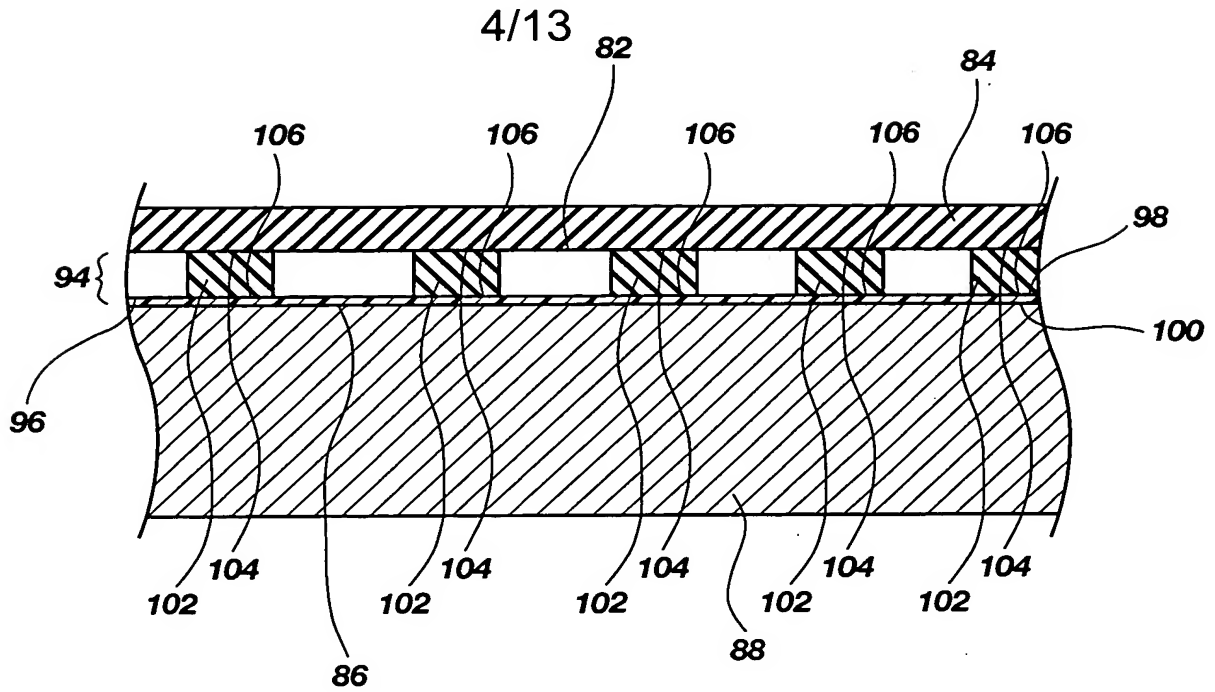


Fig. 7

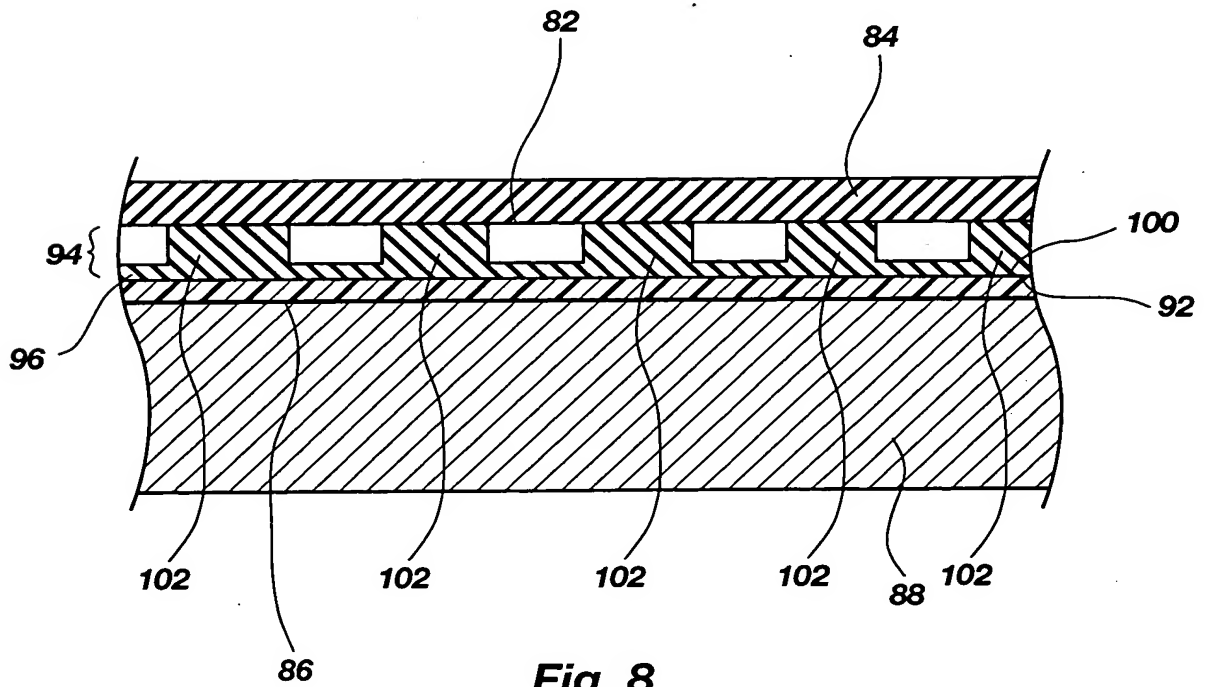


Fig. 8

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This cross-sectional view shows a semiconductor device. A substrate 88 is at the bottom, with a layer 101 on top of it. A series of rectangular regions 103 are formed in the layer 101. Above these regions, a layer 99 is deposited, which contains a series of rectangular openings 105. A top layer 97 is formed over the layer 99. A bracket 95 indicates the region containing the openings 105 and the layer 99. A label 101 also points to the substrate region.

Fig. 9

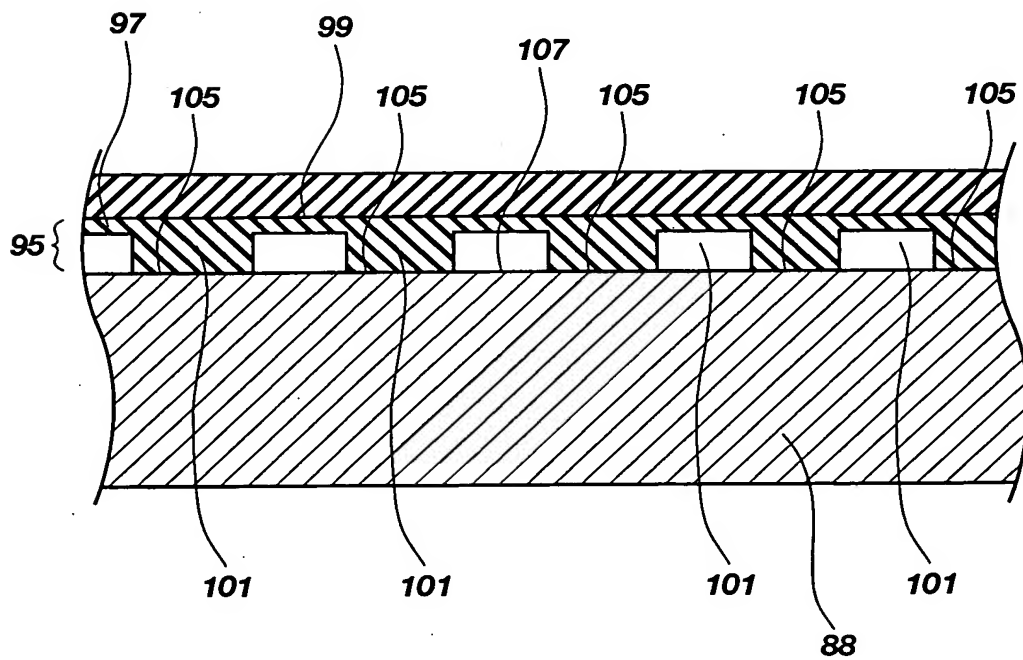


Fig. 10

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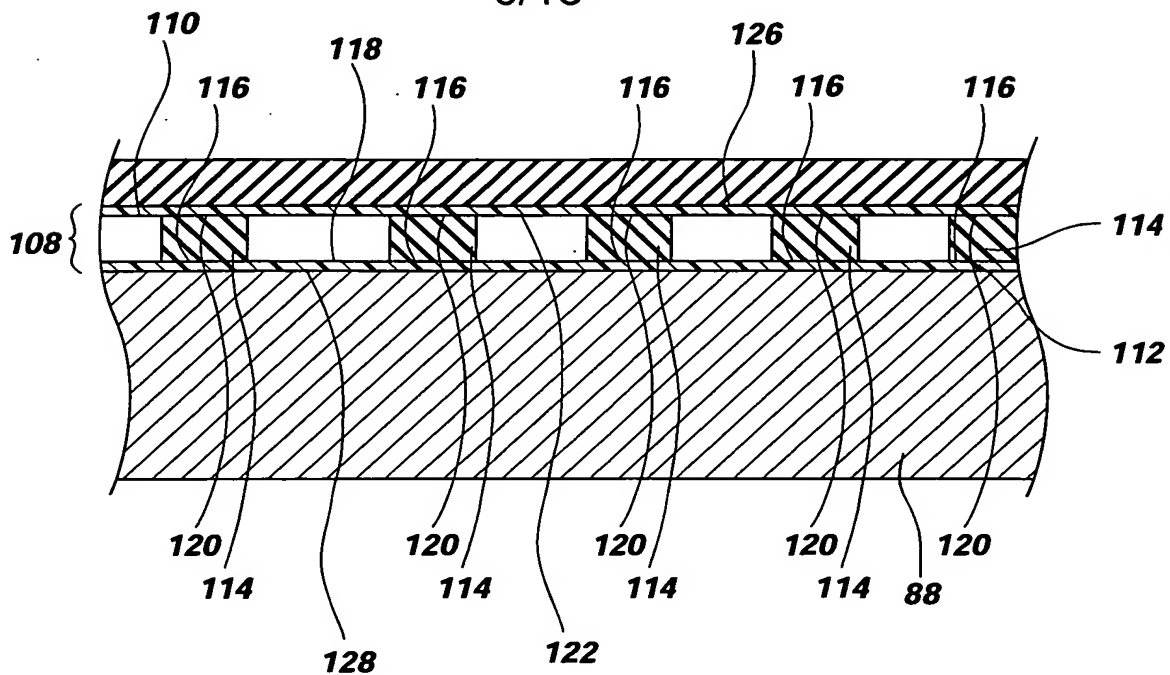


Fig. 11

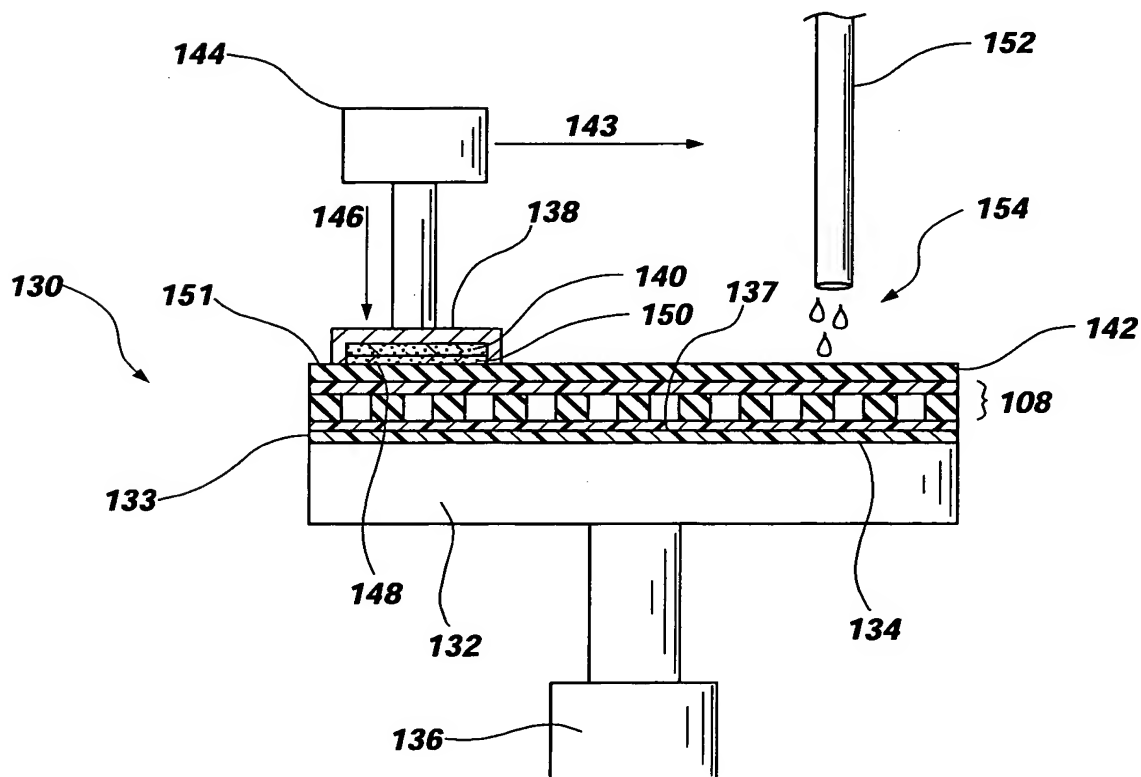


Fig. 12

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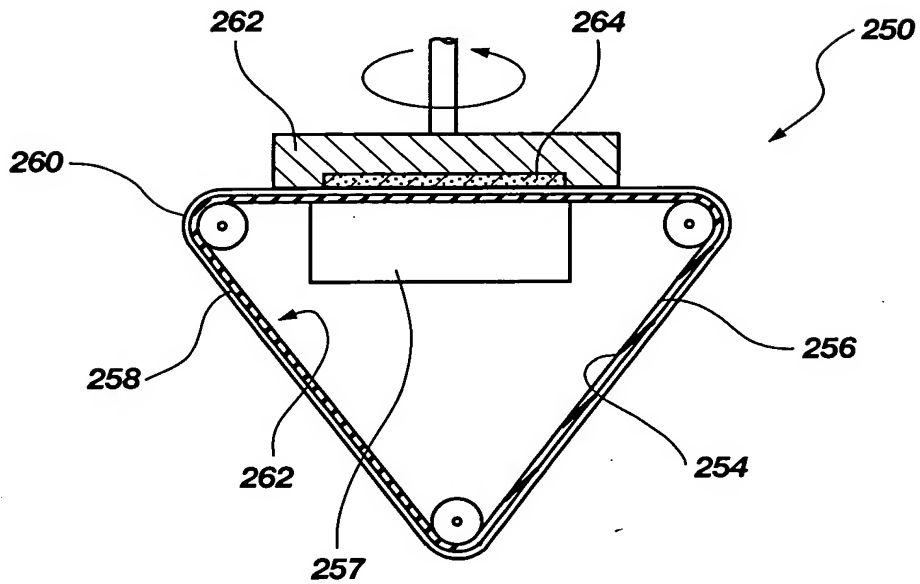


Fig. 13

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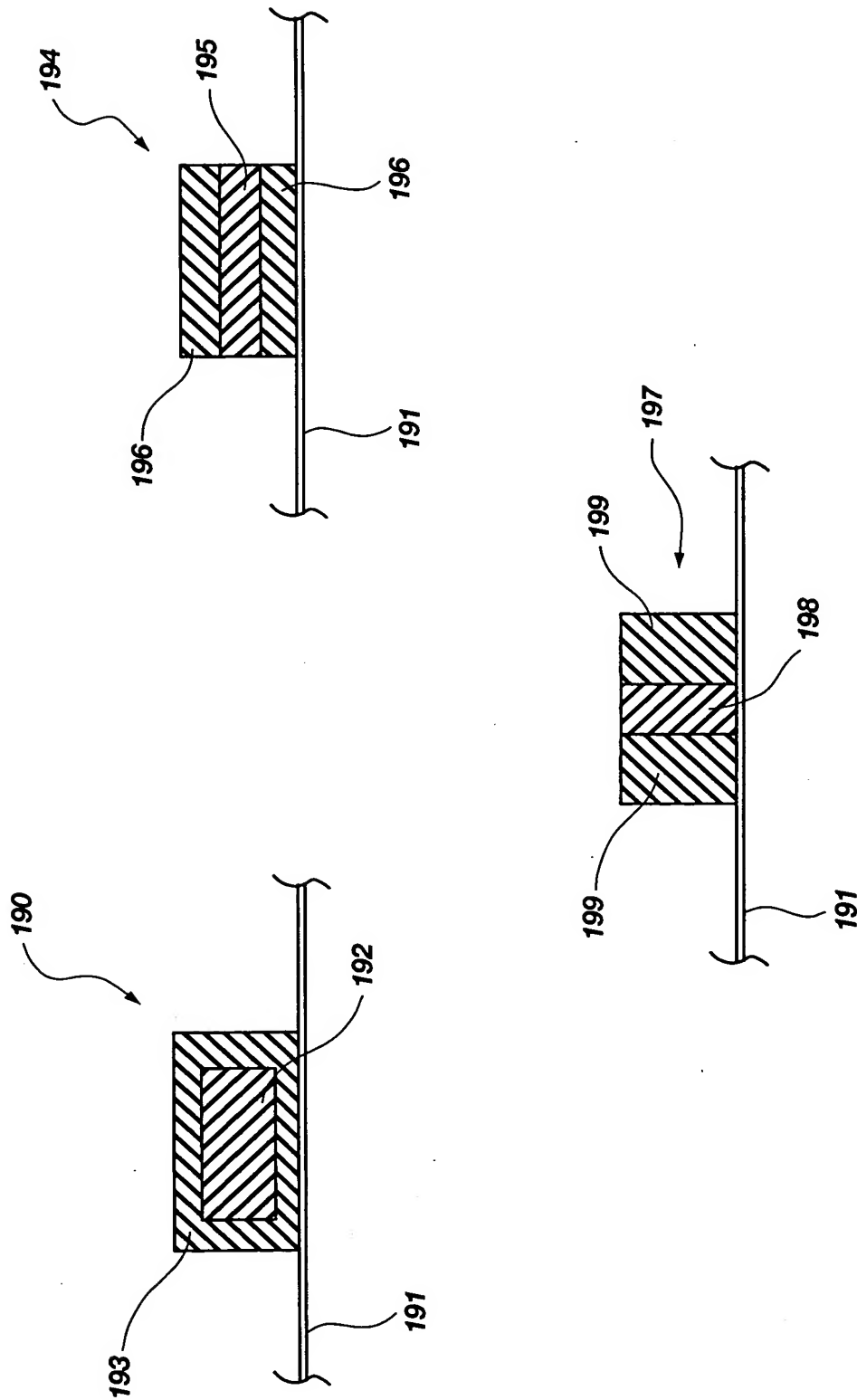


Fig. 14

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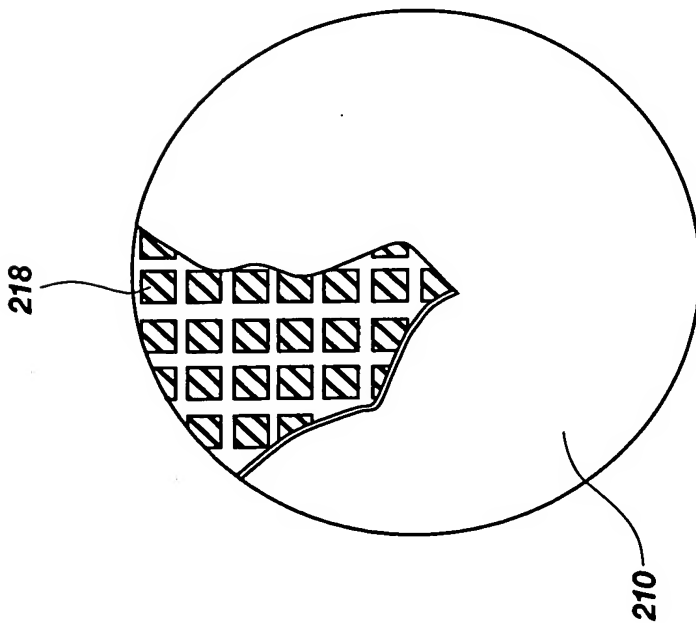
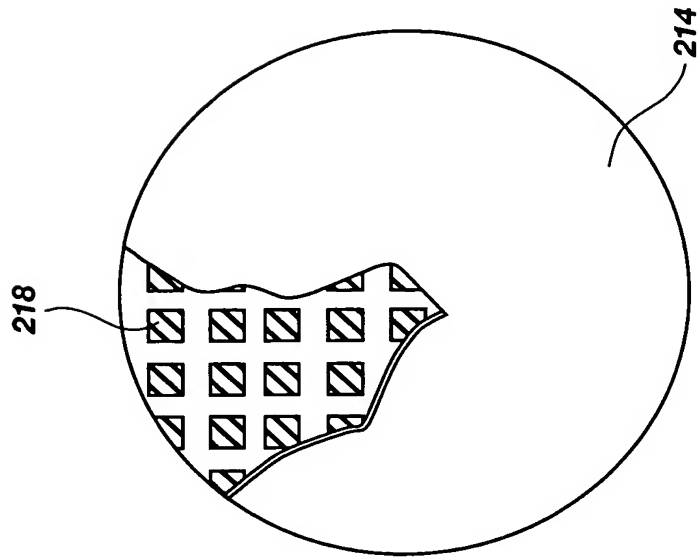


Fig. 15

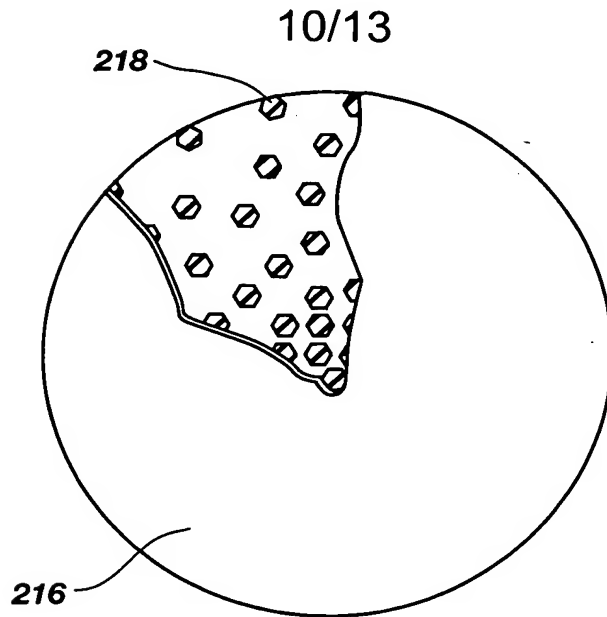


Fig. 16

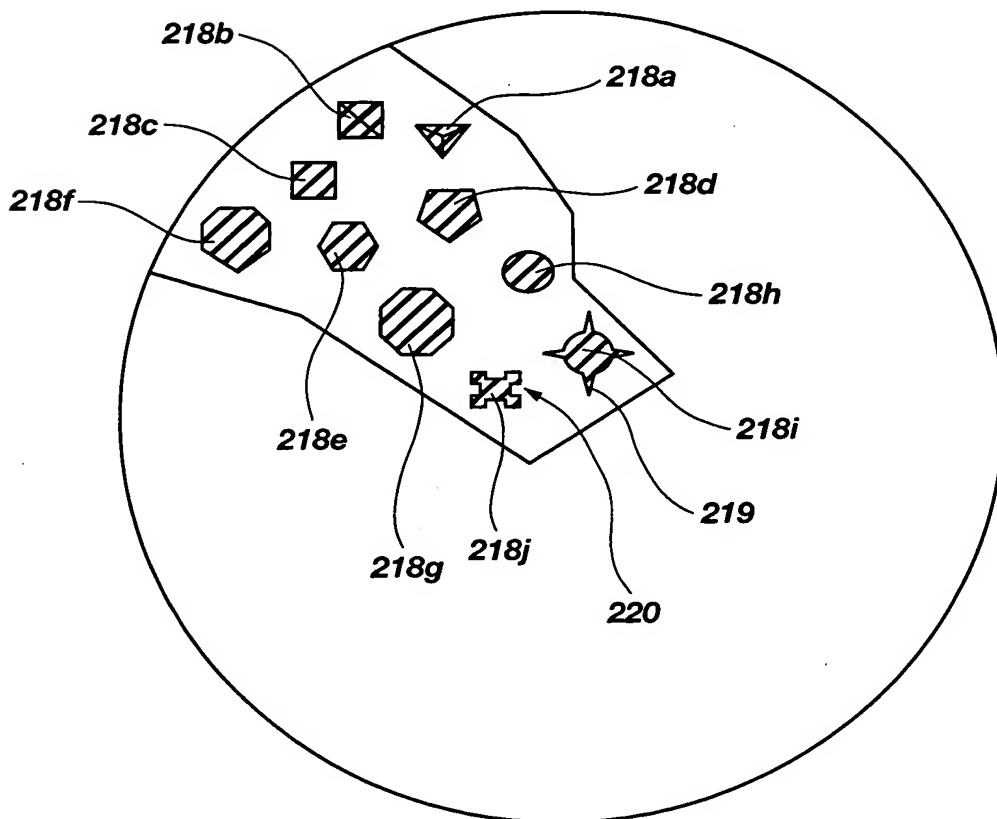


Fig. 17

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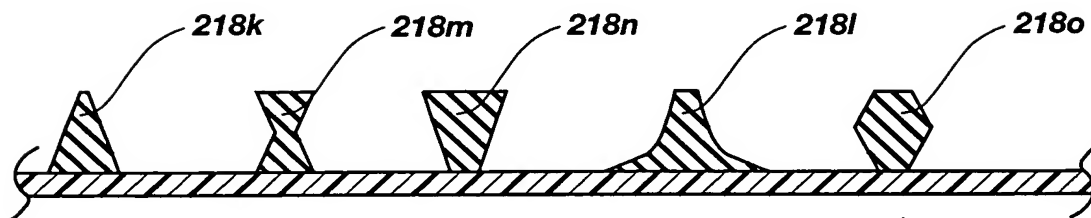


Fig. 18

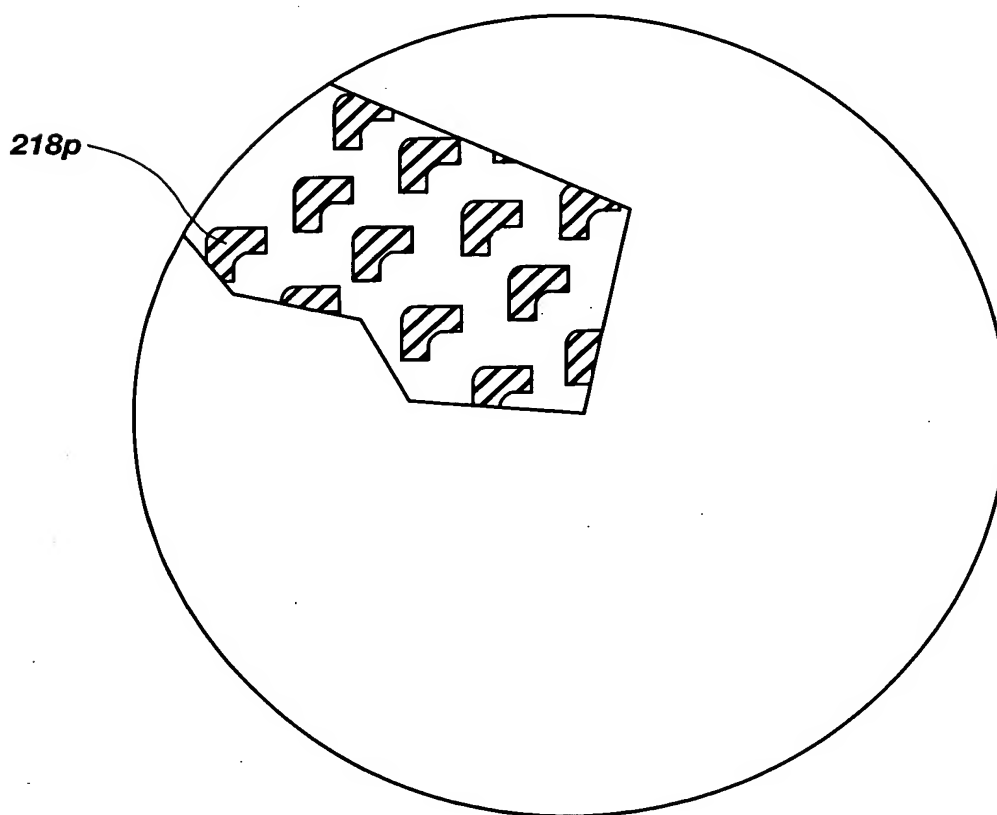


Fig. 19

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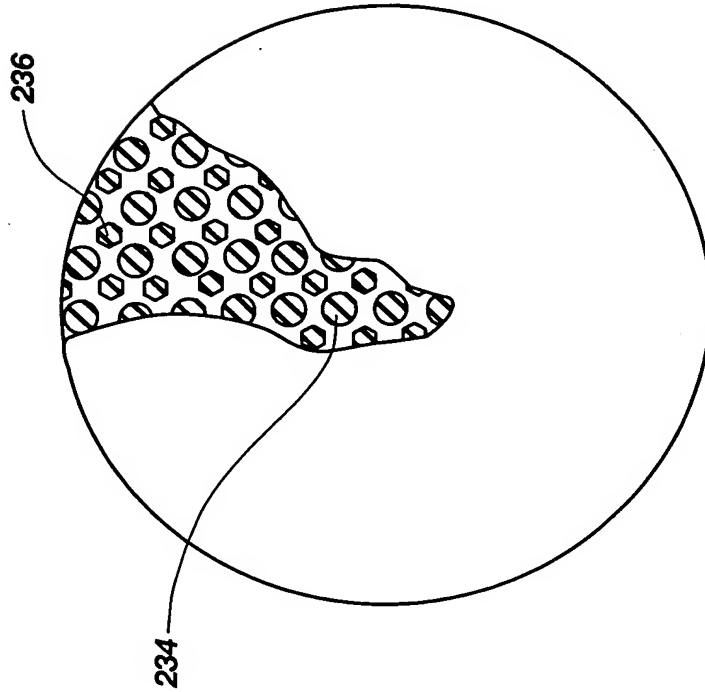


Fig. 21

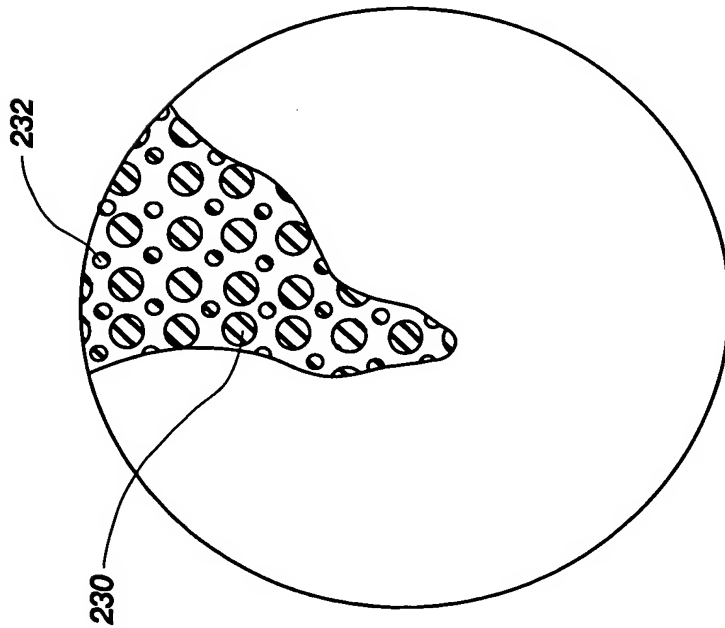


Fig. 20

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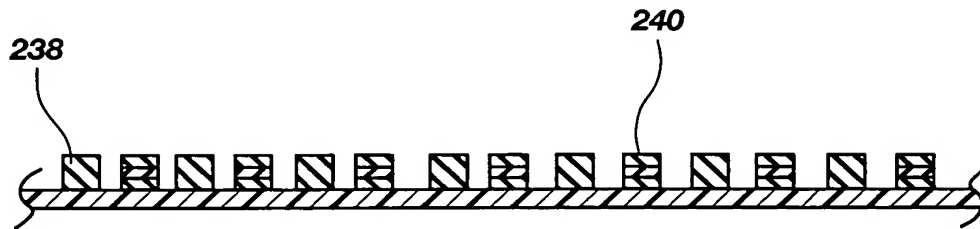


Fig. 22